Sub-5 nm structured films by hydrogen bonded siloxane liquid crystals and block copolymers

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This paper describes the synthesis and characterization of a novel class of hydrogen-bonding oligo(dimethylsiloxane)-based thermotropic liquid crystals (LCs), with which polymeric supramolecules were obtained with glassy smectic and columnar sub-5 nm features when combined with poly(4-vinylpyrine) homopolymer or poly(styrene)-b-poly(4-vinylpyrine) block copolymer (BCP). The hierarchical self-assembly afforded by the LC/BCP complexes further resulted in the vertical orientation of the LC features in thin films.

Unlike conventional diblock copolymers (BCPs), the self-assembly of small molecules is not limited by an order-disorder transition at low molecular weight, allowing the formation of sub-5 nm features, for applications including organic electronics, and ultra-fine nanolithographic resists. In particular, hybrid organic/inorganic small molecules such as those based on polyhedral oligomeric silsesquioxane (POSS) or oligo(dimethylsiloxane) (ODMS) are advantageous, since their chemical immiscibility leads to phase separation into highly ordered nanostructures and a high etch contrast between molecular components. In principle, these materials could be used to fabricate inorganic nanostructure arrays with sub-5 nm features by etching. However, there are still major challenges concerning this novel class of materials; including control over the self-assembled nanostructured morphology, the formation of defect-free patterns in thin films with a predetermined orientation, and their conversion into functional materials and devices.

We previously reported a series of ODMS liquid crystals (LCs) which form columnar and lamellar morphologies with sub-5 nm dimensions. The high mobility of LC phases makes these materials amenable to directed self-assembly processes for the formation of large-area ordered structures, such as graphoepitaxy, and photoalignment. However, obtaining vertically oriented features remains challenging given the low surface energy of ODMS (γ_{ODMS} ~ 20.4 mN/m). Moreover, the low glass transition temperature (T_g) associated with these materials (T_g, ODMS ~ -127 °C) prevents the ‘freezing-in’ of metastable structures, and could lead to the deformation of the nanopatterns during processing. To address these challenges, it would be desirable to combine the sub-5 nm feature sizes of hybrid organic/inorganic small molecules with the properties and processing of glassy polymeric materials. Glassy polymeric supramolecular assemblies (PSAs) have been constructed through the linking of small molecules to polymer side chains via noncovalent interactions such as hydrogen bonding, electrostatic interactions, or metal ligation. The main advantage of PSAs is that they enable morphological control through a modular mixing approach, as opposed to cumbersome organic synthesis. Extensive studies have been carried out on PSA systems consisting of n-alkylphenols in combination with poly(4-vinylpyrine) (P4VP) or poly(styrene)-b-poly(4-vinylpyrine) (PS-b-P4VP). Early work by the group of Ikkala showed that pentadecylyphenol (PDP) can form a smectic (Sm) LC phase in the microdomains of PS-b-P4VP. A key aspect of the hierarchical self-assembly is that the BCP features are oriented perpendicular to those formed by PDP on a smaller length scale. Since this pioneering work, other small molecules have been combined with P4VP to form PSA materials with more complex morphologies, and specific functionalities, such as perfluorocarbons, oligo(thiophenes), and azobenzences. However, hybrid organic/inorganic PSAs with sub-5nm features have not been reported. Moreover, while most studies have been limited to bulk phase behaviour, the phenomenon of hierarchical self-assembly provides opportunities for controlling the thin film orientation of features, which is important for nanofabrication.

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In this contribution, we report glassy ODMS-based PSAs which are obtained by the hydrogen bonding of an ODMS LC with P4VP and PS-b-P4VP. First, the synthesis and characterization of the novel ODMS LC is discussed, followed by the hierarchical self-assembly behaviour. By adjusting the molar fraction of the LCs within the PSA, smectic and columnar hexagonal morphologies were obtained with sub-5 nm features. The ultra-fine features were oriented vertically in thin films by using the hierarchical self-assembly approach.

Hydrogen bonding ODMS liquid crystal LC (Fig 1a) was prepared and fully characterized (Supporting information). According to temperature dependent polarized optical microscopy (POM) (Fig 1b) and differential scanning calorimetry (DSC) (Fig S1), LC exhibits a room-temperature (RT) mesophase, marked by the occurrence of birefringent multidomains (Fig 1b). Using bulk X-ray diffraction (XRD) (Fig 1c), two broad peaks were observed in the wide-angle region (6 nm⁻¹ < q > 20 nm⁻¹), signifying nano-phase separation between the ODMS (q = 9 nm⁻¹, d = 0.70 nm) and organic (q = 13.4 nm⁻¹, d = 0.45 nm) molecular components. The medium angle reflections (1 nm⁻¹ < q > 6 nm⁻¹) were used to assign a hexagonal columnar phase (Colhex) (plane group p6mm), with a lattice constant of a = 4.69 nm. The formation of a columnar phase as opposed to a smectic phase is likely a consequence of the large coil-to-rod volume fraction due to the bulky ODMS. Moreover, since the lattice constant is approximately equal to double the molecular length, (as determined by molecular simulation) the presence of the LC phase is likely driven by dimer formation (Fig 1a).

Initial hydrogen bonding experiments, performed by mixing LC with P4VP block (PDI=1.25), indicated that hydrogen bonded complexes are readily formed up to high loadings (Fig S2, Fig S3). The resulting PSAs exhibit grainy birefringent textures (Fig S4) and Tg’s of approximately 80 °C, considerably lower than that of neat P4VP (Tg ~132 °C) (Fig S5). On the basis of these initial experiments, LC was mixed with PS33k-b-P4VP (fH2O ~ 0.8) (PDI=1.06), to prepare hierarchical PSAs by selective hydrogen bonding of LC via the P4VP block (Fig 2a). Hierarchical PSAs were prepared with molar ratios x = 0.3, x = 0.4, and x = 0.5, where x = LC: PS33k-b-P4VP block. Neat PS33k-b-P4VP exhibits a hexagonal (HEX) morphology in bulk (P4VP minority phase), but is expected to form a lamellar (LAM) morphology upon addition of LC, by the increase of volume fraction of the combined P4VP block. The hierarchical PSAs exhibit comparable hydrogen-bonding behaviour and thermal transitions compared to the homopolymer system, with the exception of an additional glass transition at 120 °C, which corresponds to the PS33k domains.

The presence of distinct glass transition temperatures for PS33k (95 °C) and P4VP in LCs (80 °C) already indicates the immiscibility of the blocks. The PS33k-b-P4VP(LC) materials were investigated by bulk XRD. To capture the hierarchical multi-scale self-assembly, scattering data was obtained in small-angle and medium-angle configurations. Fig 2b shows the combined data (concatenated at q = 0.7 nm⁻¹) together with the assigned lattice constants and Miller indices. For x = 0.3, a smectic-in-lamellar (Sm-in-LAM) phase is observed (d = 37.0 nm, a = 5.81 nm). For x = 0.5, a Colhex-in-LAM phase is observed (d = 40.6 nm, a = 6.3 nm) and at the intermediate molar ratio (x = 0.4) a combination of medium angle scatterings are observed in addition to the LAM morphology of the BCP, indicating the co-existence of Sm and Colhex morphologies (mixed-in-LAM). Overall, the lamellar spacing increases slightly with increasing x, likely due to the increase in combined molecular weight (d ~N²/3). The Sm to Colhex transition can be understood by volumetric arguments, and suggests that the vinyl(pyridines) are at the centre of the supramolecular cylinders in the Colhex phase. 2D XRD plots of shear-aligned samples further indicate the orthogonal nature of the hierarchical self-assembly (Fig S6). In order to visualise the
hierarchical nature of the self-assembly, transmission electron microscopy (TEM) was performed on a PS_{33k-b-P4VP_{15k}(LC)}_{0.5} thin film. To this end, thick films were prepared by dropcasting on an epoxy substrate, and solvo-thermal annealed with chloroform to promote ordering. Large area TEM images of different unstained polymer sections reveal the presence of alternating layered structures with high lateral order across the image (Fig. S7). Within the layers, smaller features are contained. Analysis of a zoomed-in image (Fig 2c) reveals that the layered structures have a periodicity of ca. 35 nm, corresponding to the BCP lattice spacing. Perpendicular to these lamellae, features with a periodicity of ca. 6 nm are observed, corresponding the LC phase of the P4VP_{15k}(LC)_{0.5} component. Interestingly, the morphology at the interface between the PSA and the epoxy substrate (Fig 3d) shows that the PSA is directed at the substrate interface. The BCP lamellae are oriented parallel to the epoxy substrate, and by extension, the LC features are oriented in a perpendicular fashion. Moreover, the interface layer appears to consist of an LC layer.

For nanofabrication purposes, vertically oriented Sm features must be achieved in thin films. In order to investigate the effect of hierarchical PSAs on the thin film orientation of LC features, thin films were prepared by spin-coating dilute solutions of P4VP_{15k}(LC) and PS_{33k-b-P4VP_{15k}(LC)}_{0.5} on Si wafers bearing an antireflective coating. Solutions of 2 wt % in chloroform resulted in ca. 80 nm thin films, according to ellipsometry. The cast films where thermally annealed at 85°C for 1h to develop large-area alignment, which was not present in as-cast films (Fig S8). Fig 3 shows the characterization data for Sm PSAs P4VP_{15k}(LC)_{0.4} and PS_{33k-b-P4VP_{15k}(LC)}_{0.3}. Fig 3a shows the atomic force microscopy (AFM) height map for P4VP_{15k}(LC)_{0.4} which is marked by the presence of distinct plateaus. According to the cross-section (shown by the black line), the height of the plateaus are ca. 6 nm, which corresponds to the smectic layer spacing expected for this material, and indicate the presence of smectic layers which are oriented parallel to the surface. Since the surface energy of the ODMs tails is presumed to be very low (\gamma_{ODMS} = 20.5 mN/m), the siloxane tails are anticipated to wet the air interface, driving the parallel orientation. In contrast, for PS_{33k-b-P4VP_{15k}(LC)}_{0.3}, (Fig 3b) plateaus are observed with a height of ca. 37 nm, corresponding to the BCP layer spacing. This finding implies the parallel orientation of BCP features, and by extension, the vertical alignment of LC features inside the film. To investigate the through-film morphology of the annealed films, small-angle grazing-incidence x-ray diffraction (GIXRD) was performed. Fig 3c shows that the scattering data for P4VP_{15k}(LC)_{0.4} can be fitted assuming a smectic phase (a = 6.0 nm) in which the smectic layers are oriented parallel to the surface, in agreement with AFM observations. In contrast, for PS_{33k-b-P4VP_{15k}(LC)}_{0.3}, the scattering peaks are oriented parallel to the substrate, indicating that the smectic features are oriented normal to the surface. The absence of diffraction rods originating from the BCP lamellae, indicate indirectly that they are oriented planar to the surface. For the LC cylinders in the Col_{hex} phase, similar observations are made (Fig S9). Together, these findings indicate that the presence of the PS block causes the vertical alignment for both Sm and Col_{hex} LC features.

![Fig 2: a) Chemical structures of polymeric supramolecular assembly of PS_{33k-b-P4VP_{15k}(LC)}x. The carboxylic group on LC associates selectively with the pyridine group on P4VP via hydrogen bonding. b) Bulk x-ray diffraction data of the PS_{33k-b-P4VP_{15k}(LC)}x polymeric supramolecular assemblies. The XRD spectra were collected in the small-angle and medium-angle configuration, and concatenated at q = 0.7 nm^{-1}. The assigned Miller indices and the respective intermolecular scatterings are indicated, as well as the corresponding lattices. P4VP + hydrogen bonding core = red, ODMs tail = blue, PS = yellow. Sm = Smectic, LAM = lamellar, Col_{hex} = columnar hexagonal. c-d) Transmission electron micrographs of PS_{33k-b-P4VP_{4k}(LC)}_{0.5} on an epoxy substrate. PS lamellae are light; ODMS side chains are dark. d) TEM image of the PSA at the epoxy interface (inset = 2x magnification).]
**Conclusions**

In conclusion, novel hydrogen bonding ODMS LCs were prepared, characterized, and their thermotropic phase behavior was investigated. The LCs were subsequently mixed with a glassy hydrogen-bond accepting polymer (P4VP) and selectively hydrogen-bond accepting block copolymer (PS-b-P4VP) in various molar ratios. This modular approach results in the formation of a range of glassy nanostructured morphologies in which the phase behavior can be controlled by the mixing ratio. By mixing the LCs with a block copolymer, oriented hierarchical structures were generated, including Sm-in-LAM and ColHex-in-LAM morphologies. The synergistic co-assembly was used to obtain vertical alignment of the sub-5 nm Sm and ColHex features, which could lead to the fabrication of dense line spaces and contact holes, respectively. In perspective, the sandwiching of the sub-5 nm LC features between PS lamellae to achieve the vertical orientation of low surface energy ODMS, has the potential to eliminate the need for a top-coat (to control surface-air interactions), a neutral brush layer at the interface of the substrate, or photoalignment. In order to move towards the utilization of these materials as high etch contrast, glassy, self-assembled resists, monolayer “sandwich” structures must be prepared by adjusting the spin-coating parameters, followed by the removal of the polymeric top layer using dry etching techniques. This work, together with etching and pattern transfer to yield inorganic sub-5 nm features, will be the subject of future investigations.

**Conflicts of interest**

There are no conflicts to declare.

**References**
